USE OF PARTICULAR MIXTURES OF ETHYL LACTATE AND METHYL ETHYL KETONE TO REMOVE UNDESIRABLE PERIPHERAL MATERIAL (E.G. EDGE BEADS) FROM PHOTORESEST-COATED SUBSTRATES

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Filed: Jul. 31, 1989

Related U.S. Application Data
Division of Ser. No. 141,128, Jan. 6, 1988, Pat. No. 4,886,728.

Int. Cl. ‐ B01F 1/00
U.S. Cl. 252/364; 524/317; 524/364; 430/331
Field of Search 524/317, 364; 252/364; 430/331

A process for removing unwanted photoresist material from the peripheral areas of a photoresist substrate comprising the steps of:
(a) spin coating a photoresist solution onto a surface of a substrate, thereby applying a photoresist coating which comprises a uniform film over substantially all of said substrate surface except for unwanted photoresist material deposits at the peripheral areas of said surface;
(b) contacting said peripheral area of the coated substrate with a sufficient amount of a solvent mixture comprising a mixture of ethyl lactate and methyl ethyl ketone present in a volume ratio of about 65:35 to about 25:75, respectively, to selectively dissolve said unwanted deposits without adversely affecting said uniform film; and
(c) separating said dissolved deposits from said coated substrate.

3 Claims, No Drawings